ABSTRACT

METHOD AND APPARATUS FOR CHEMICAL VAPOR DEPOSITION

Methods of depositing compound semiconductors onto substrates (20) are disclosed, including directing gaseous reactants (30, 34) into a reaction chamber (10) containing the substrates (20), selectively supplying energy (31a, 31b) to one of the gaseous reactants (30, 34) in order to impart sufficient energy to activate that reactant but insufficient to decompose the reactant, and then decomposing the reactant at the surface of the substrate (20) in order to react with the other reactants. The preferred energy source (31a, 31b) is microwave or infrared radiation, and reactors (10) for carrying out these methods are also disclosed.

FIG. 1